

=> :
Uploading C:\Program Files\Stnexp\Queries\10799864-1.str

L6 STRUCTURE UPLOADED

=> que L6 AND L5

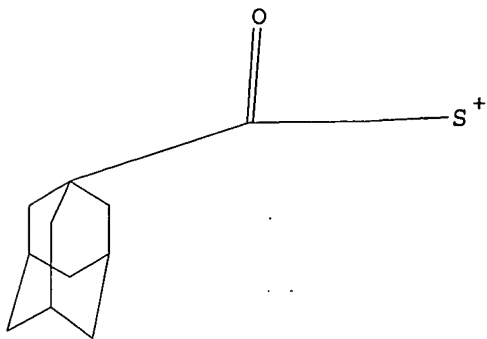
L7 QUE L6 AND L5

=> d

L7 HAS NO ANSWERS

L5 SCR 2040

L6 STR



Structure attributes must be viewed using STN Express query preparation.

L7 QUE ABB=ON PLU=ON L6 AND L5

=> s l7 sss sam

SAMPLE SEARCH INITIATED 19:05:06 FILE 'REGISTRY'

SAMPLE SCREEN SEARCH COMPLETED - 12 TO ITERATE

100.0% PROCESSED 12 ITERATIONS

3 ANSWERS

SEARCH TIME: 00.00.01

FULL FILE PROJECTIONS: ONLINE **COMPLETE**

BATCH **COMPLETE**

PROJECTED ITERATIONS: 33 TO 447

PROJECTED ANSWERS: 3 TO 163

L8 3 SEA SSS SAM L6 AND L5

=>Testing the current file.... screen

ENTER SCREEN EXPRESSION OR (END):end

=> screen 2040

L9 SCREEN CREATED

=>

Uploading C:\Program Files\Stnexp\Queries\10799864-3.str

L10 STRUCTURE UPLOADED

=> que L10 AND L9

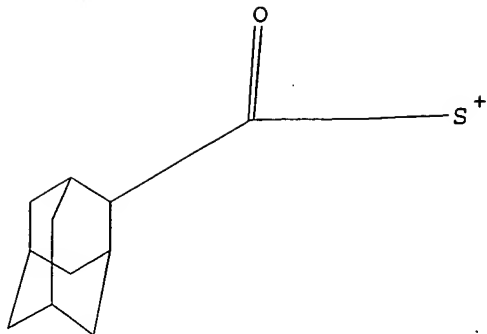
L11 QUE L10 AND L9

=> d

L11 HAS NO ANSWERS

L9 SCR 2040

L10 STR



Structure attributes must be viewed using STN Express query preparation.
 L11 QUE ABB=ON PLU=ON L10 AND L9

=> s l11 sss sam

SAMPLE SEARCH INITIATED 19:05:23 FILE 'REGISTRY'
 SAMPLE SCREEN SEARCH COMPLETED - 12 TO ITERATE

100.0% PROCESSED 12 ITERATIONS 0 ANSWERS
 SEARCH TIME: 00.00.01

FULL FILE PROJECTIONS: ONLINE **COMPLETE**
 BATCH **COMPLETE**
 PROJECTED ITERATIONS: 33 TO 447
 PROJECTED ANSWERS: 0 TO 0

L12 0 SEA SSS SAM L10 AND L9

=> d his

(FILE 'HOME' ENTERED AT 19:02:21 ON 23 MAY 2005)

FILE 'REGISTRY' ENTERED AT 19:02:33 ON 23 MAY 2005

L1 SCREEN 2040
 L2 STRUCTURE UPLOADED
 L3 QUE L2 AND L1
 L4 50 S L3 SSS SAM

FILE 'HOME' ENTERED AT 19:03:10 ON 23 MAY 2005

FILE 'REGISTRY' ENTERED AT 19:04:35 ON 23 MAY 2005

L5 SCREEN 2040
 L6 STRUCTURE UPLOADED
 L7 QUE L6 AND L5
 L8 3 S L7 SSS SAM
 L9 SCREEN 2040
 L10 STRUCTURE UPLOADED
 L11 QUE L10 AND L9
 L12 0 S L11 SSS SAM

=> FIL HCAPLUS, CAPLUS, USPATFULL

COST IN U.S. DOLLARS	SINCE FILE ENTRY	TOTAL SESSION
FULL ESTIMATED COST	0.86	1.92

FILE 'HCAPLUS' ENTERED AT 19:05:35 ON 23 MAY 2005
 USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.
 PLEASE SEE "HELP USAGETERMS" FOR DETAILS.
 COPYRIGHT (C) 2005 AMERICAN CHEMICAL SOCIETY (ACS)

FILE 'CAPLUS' ENTERED AT 19:05:35 ON 23 MAY 2005
 USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.

PLEASE SEE "HELP USAGETERMS" FOR DETAILS.
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FILE 'USPATFULL' ENTERED AT 19:05:35 ON 23 MAY 2005
CA INDEXING COPYRIGHT (C) 2005 AMERICAN CHEMICAL SOCIETY (ACS)

=> s l4 or l8 or l12
L13 90 L4 OR L8 OR L12

=> duplicates remove l13
DUPLICATE PREFERENCE IS 'HCAPLUS, CAPLUS, USPATFULL'
KEEP DUPLICATES FROM MORE THAN ONE FILE? Y/(N):n
PROCESSING COMPLETED FOR L13
L14 45 DUPLICATE REMOVE L13 (45 DUPLICATES REMOVED)

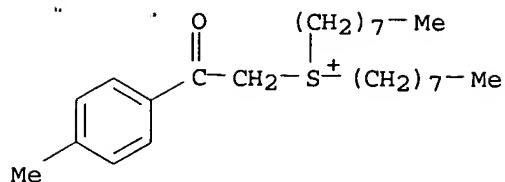
=> s l14 and (resist or photoresist)
L15 12 L14 AND (RESIST OR PHOTORESIST)

=> duplicates remove l15
DUPLICATE PREFERENCE IS 'HCAPLUS, USPATFULL'
KEEP DUPLICATES FROM MORE THAN ONE FILE? Y/(N):n
PROCESSING COMPLETED FOR L15
L16 12 DUPLICATE REMOVE L15 (0 DUPLICATES REMOVED)

=> d l16 1-12 ibib hitstr

L16 ANSWER 1 OF 12 HCAPLUS COPYRIGHT 2005 ACS on STN
ACCESSION NUMBER: 2005:78066 HCAPLUS
DOCUMENT NUMBER: 142:186539
TITLE: Positive photosensitive composition and method of
forming **resist** pattern
INVENTOR(S): Kodama, Kunihiro
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: U.S. Pat. Appl. Publ., 48 pp.
CODEN: USXXCO
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 2005019690	A1	20050127	US 2004-895824	20040722
EP 1505439	A2	20050209	EP 2004-17305	20040722
EP 1505439	A3	20050420		
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, PL, SK, HR				
JP 2005055890	A2	20050303	JP 2004-215380	20040723
PRIORITY APPLN. INFO.:			JP 2003-278995	A 20030724
IT 769952-29-6				
RL:	TEM (Technical or engineered material use); USES (Uses) (photoacid generator; pos. photosensitive composition for forming resist pattern containing)			
RN 769952-29-6	HCAPLUS			
CN	Sulfonium, [2-(4-methylphenyl)-2-oxoethyl]dioctyl-, salt with 1,1,2,2,3,3,4,4,4-nonafluoro-1-butanefluorobutanesulfonic acid (1:1) (9CI) (CA INDEX NAME)			
CM	1			
CRN	769952-28-5			
CMF	C25 H43 O S			



CM 2

CRN 45187-15-3

CMF C4 F9 O3 S

-O₃S- (CF₂)₃-CF₃

L16 ANSWER 2 OF 12 HCAPLUS COPYRIGHT 2005 ACS on STN

ACCESSION NUMBER: 2005:275941 HCAPLUS

DOCUMENT NUMBER: 142:363767

TITLE: Stimuli-sensitive **photoresists**, acid or radical generators therefor, and patterning thereof

INVENTOR(S): Kodama, Kunihiro

PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 81 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2005084240	A2	20050331	JP 2003-314219	20030905
PRIORITY APPLN. INFO.:			JP 2003-314219	20030905

IT **848864-08-4**

RL: CAT (Catalyst use); TEM (Technical or engineered material use); USES (Uses)

(photoacid generators; stimuli-sensitive photoacid generators for **photoresists** with small PEB temperature dependency)

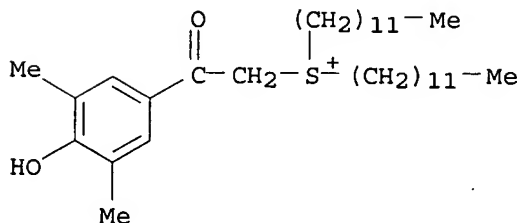
RN 848864-08-4 HCAPLUS

CN Sulfonium, didodecyl[2-(4-hydroxy-3,5-dimethylphenyl)-2-oxoethyl]-, salt with 3,5-bis(trifluoromethyl)benzenesulfonic acid (1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 848864-07-3

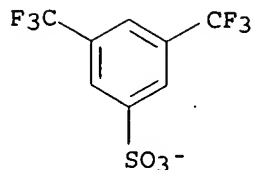
CMF C34 H61 O2 S



CM 2

CRN 213740-84-2

CMF C8 H3 F6 O3 S



L16 ANSWER 3 OF 12 HCAPLUS COPYRIGHT 2005 ACS on STN

ACCESSION NUMBER: 2004:780222 HCAPLUS

DOCUMENT NUMBER: 141:304282

TITLE: Stimulus sensitive compound such as light-sensitive acid or radical precursors and stimulus sensitive composition containing the same

INVENTOR(S): Kodama, Kunihiro; Takahashi, Hyou

PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan

SOURCE: U.S. Pat. Appl. Publ., 56 pp.

CODEN: USXXCO

DOCUMENT TYPE: Patent

LANGUAGE: English

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 2004185378	A1	20040923	US 2004-799864	20040315
JP 2004277303	A2	20041007	JP 2003-68447	20030313
PRIORITY APPLN. INFO.:			JP 2003-68447	A 20030313

OTHER SOURCE(S): MARPAT 141:304282

IT 761458-94-0P 761458-97-3P

RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(stimulus sensitive compound)

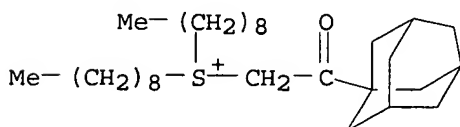
RN 761458-94-0 HCAPLUS

CN Sulfonium, dinonyl (2-oxo-2-tricyclo[3.3.1.1^{3,7}]dec-1-ylethyl)-, salt with 1,1,2,2,3,3,4,4,5,5,6,6,7,7,8,8,8-heptadecafluoro-1-octanesulfonic acid (1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 761458-93-9

CMF C30 H55 O S



CM 2

CRN 45298-90-6

CMF C8 F17 O3 S

-O₃S- (CF₂)₇-CF₃

RN 761458-97-3 HCAPLUS

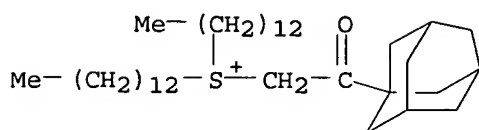
CN Sulfonium, (2-oxo-2-tricyclo[3.3.1.1^{3,7}]dec-1-ylethyl)ditridecyl-, salt with trifluoromethanesulfonic acid (1:1) (9CI) (CA INDEX NAME)

present

CM 1

CRN 761458-95-1

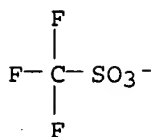
CMF C38 H71 O S



CM 2

CRN 37181-39-8

CMF C F3 O3 S



L16 ANSWER 4 OF 12 HCAPLUS COPYRIGHT 2005 ACS on STN

ACCESSION NUMBER: 2004:823478 HCAPLUS

DOCUMENT NUMBER: 141:340384

TITLE: Positive-working **photoresist** composition
containing specific acid generator

INVENTOR(S): Takahashi, Akira; Kodama, Kunihiro; Kawabe, Yasumasa

PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 57 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2004279576	A2	20041007	JP 2003-68448	20030313
PRIORITY APPLN. INFO.:			JP 2003-68448	20030313

OTHER SOURCE(S): MARPAT 141:340384

IT 769952-29-6

RL: TEM (Technical or engineered material use); USES (Uses)
(acid generator in pos.-working **photoresist** composition)

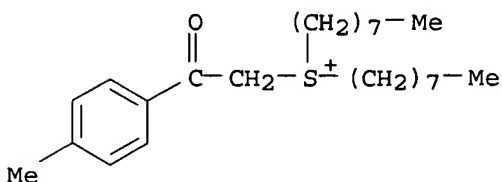
RN 769952-29-6 HCAPLUS

CN Sulfonium, [2-(4-methylphenyl)-2-oxoethyl]dioctyl-, salt with
1,1,2,2,3,3,4,4,4-nonafluoro-1-butanesulfonic acid (1:1) (9CI) (CA INDEX
NAME)

CM 1

CRN 769952-28-5

CMF C25 H43 O S



CM 2

CRN 45187-15-3
CMF C4 F9 O3 S

$^{-}O_3S-(CF_2)_3-CF_3$

L16 ANSWER 5 OF 12 HCAPLUS COPYRIGHT 2005 ACS on STN

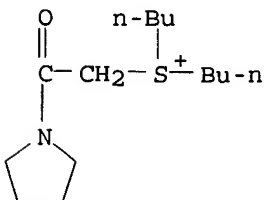
ACCESSION NUMBER: 2003:853314 HCAPLUS
DOCUMENT NUMBER: 139:343479
TITLE: Sulfonium compounds as radiation-sensitive acid generators and **resist** compositions containing them
INVENTOR(S): Kodama, Kunihiro
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 66 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2003307839	A2	20031031	JP 2002-112372	20020415
PRIORITY APPLN. INFO.:			JP 2002-112372	20020415
OTHER SOURCE(S):	MARPAT	139:343479		

IT 617692-33-8
RL: CAT (Catalyst use); USES (Uses)
(preparation of sulfonium compds. having amide or sulfonamide linkage as radiation-sensitive acid generators and **resist** compns. containing them)
RN 617692-33-8 HCAPLUS
CN Sulfonium, dibutyl[2-oxo-2-(1-pyrrolidinyl)ethyl]-, salt with 1,1,2,2,3,3,4,4,4-nonafluoro-1-butanefulfonic acid (1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 617692-32-7
CMF C14 H28 N O S



CM 2

CRN 45187-15-3
CMF C4 F9 O3 S

$^{-}O_3S-(CF_2)_3-CF_3$

L16 ANSWER 6 OF 12 USPATFULL on STN

ACCESSION NUMBER: 2003:300936 USPATFULL
 TITLE: Polymerizable composition
 INVENTOR(S): Uesugi, Takahiko, Tokyo, JAPAN
 Arishima, Masashi, Tokyo, JAPAN
 Yagi, Tadao, Tokyo, JAPAN

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 2003212162	A1	20031113
APPLICATION INFO.:	US 2002-276307	A1	20021122 (10)
	WO 2002-JP2303		20020312

	NUMBER	DATE
PRIORITY INFORMATION:	JP 2001-67938	20010312
DOCUMENT TYPE:	Utility	
FILE SEGMENT:	APPLICATION	
LEGAL REPRESENTATIVE:	OBLON, SPIVAK, MCCLELLAND, MAIER & NEUSTADT, P.C., 1940 DUKE STREET, ALEXANDRIA, VA, 22314	
NUMBER OF CLAIMS:	5	
EXEMPLARY CLAIM:	1	
NUMBER OF DRAWINGS:	3 Drawing Page(s)	
LINE COUNT:	1607	

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

IT 457645-95-3P

(initiators for highly UV-sensitive radically polymerizable compns.
 without sensitizers)

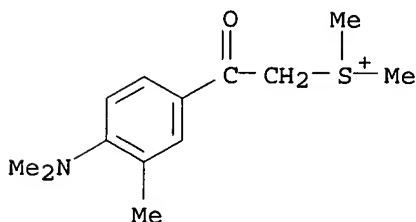
RN 457645-95-3 USPATFULL

CN Sulfonium, [2-[4-(dimethylamino)-3-methylphenyl]-2-oxoethyl]dimethyl-,
 tetraphenylborate(1-) (9CI) (CA INDEX NAME)

CM 1

CRN 457645-94-2

CMF C13 H20 N O S

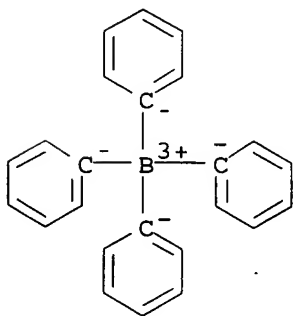


CM 2

CRN 4358-26-3

CMF C24 H20 B

CCI CCS

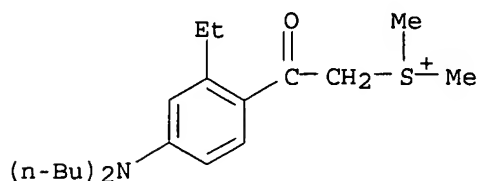


IT 457645-60-2

(initiators for highly UV-sensitive radically polymerizable compns.
without sensitizers)

RN 457645-60-2 USPATFULL

CN Sulfonium, [2-[4-(dibutylamino)-2-ethylphenyl]-2-oxoethyl]dimethyl-,
bromide (9CI) (CA INDEX NAME)



● Br⁻

L16 ANSWER 7 OF 12 HCAPLUS COPYRIGHT 2005 ACS on STN

ACCESSION NUMBER: 2002:707243 HCAPLUS

DOCUMENT NUMBER: 137:217798

TITLE: Highly UV-sensitive radically polymerizable
compositions without sensitizers

INVENTOR(S): Uesugi, Takahiko; Arishima, Shinji; Yagi, Tamao

PATENT ASSIGNEE(S): Toyo Ink Mfg. Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 23 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2002265512	A2	20020918	JP 2001-67938	20010312
WO 2002072640	A1	20020919	WO 2002-JP2303	20020312
W: CN, KR, US				
RW: AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE, TR				
US 2003212162	A1	20031113	US 2002-276307	20021122
PRIORITY APPLN. INFO.:			JP 2001-67938	A 20010312
			WO 2002-JP2303	W 20020312

OTHER SOURCE(S): MARPAT 137:217798

IT 457645-95-3P

RL: CAT (Catalyst use); IMF (Industrial manufacture); PREP (Preparation);
USES (Uses)

(initiators for highly UV-sensitive radically polymerizable compns.
without sensitizers)

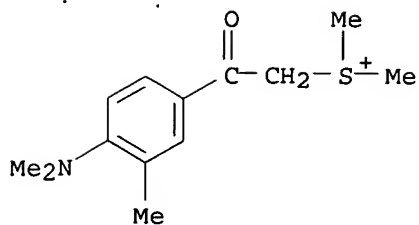
RN 457645-95-3 HCAPLUS

CN Sulfonium, [2-[4-(dimethylamino)-3-methylphenyl]-2-oxoethyl]dimethyl-,
tetraphenylborate(1-) (9CI) (CA INDEX NAME)

CM 1

CRN 457645-94-2

CMF C13 H20 N O S

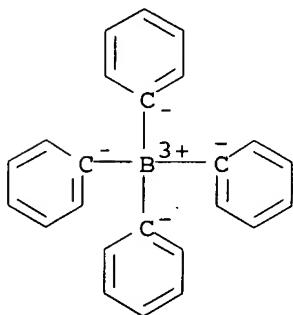


CM 2

CRN 4358-26-3

CMF C24 H20 B

CCI CCS

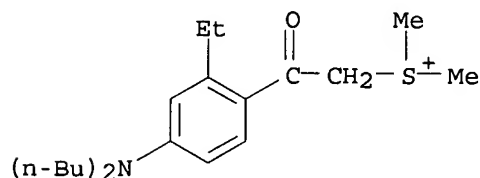


IT 457645-60-2

RL: RCT (Reactant); RACT (Reactant or reagent)
(initiators for highly UV-sensitive radically polymerizable compns.
without sensitizers)

RN 457645-60-2 HCAPLUS

CN Sulfonium, [2-[4-(dibutylamino)-2-ethylphenyl]-2-oxoethyl]dimethyl-,
bromide (9CI) (CA INDEX NAME)



● Br⁻

L16 ANSWER 8 OF 12 HCAPLUS COPYRIGHT 2005 ACS on STN

ACCESSION NUMBER: 1998:25410 HCAPLUS

DOCUMENT NUMBER: 128:128759

TITLE: Radiation-sensitive acid generator compositions,
curable compositions, positively working compositions,
and image recording compositions thereof

INVENTOR(S): Toba, Yasumasa; Tanaka, Yasuhiro; Yasuike, Madoaka;
Ichimura, Kunihiro

PATENT ASSIGNEE(S): Toyo Ink Mfg. Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 51 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 10001508	A2	19980106	JP 1996-155068	19960617

PRIORITY APPLN. INFO.:
OTHER SOURCE(S): MARPAT 128:128759

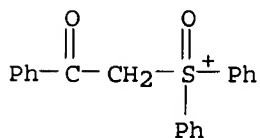
IT 194470-21-8
RL: CAT (Catalyst use); USES (Uses)
(acid generator; radiation-sensitive catalyst compns. containing
onium-borate complexes and promoters and their pos.-working and image
recording compns.)

RN 194470-21-8 HCAPLUS
CN Sulfoxonium, (2-oxo-2-phenylethyl)diphenyl-, tetrakis(pentafluorophenyl)bo
rate(1-) (9CI) (CA INDEX NAME)

CM 1

CRN 80621-37-0

CMF C20 H17 O2 S

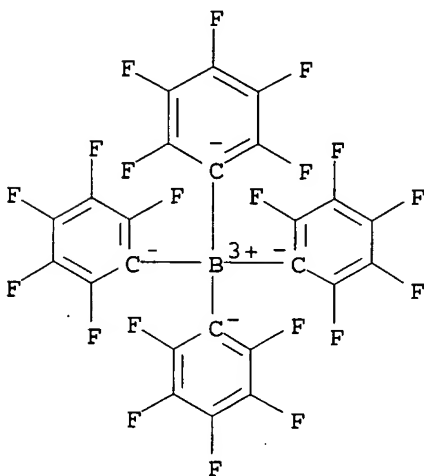


CM 2

CRN 47855-94-7

CMF C24 B F20

CCI CCS



L16 ANSWER 9 OF 12 HCAPLUS COPYRIGHT 2005 ACS on STN

ACCESSION NUMBER: 1998:8664 HCAPLUS

DOCUMENT NUMBER: 128:115380

TITLE: Sulfonium complex polymerization initiators, initiator compositions and polymerizable compositions containing the same, and their cured products

INVENTOR(S): Toba, Yasumasa

PATENT ASSIGNEE(S): Toyo Ink Mfg. Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 31 pp.

CODEN: JKXXAF

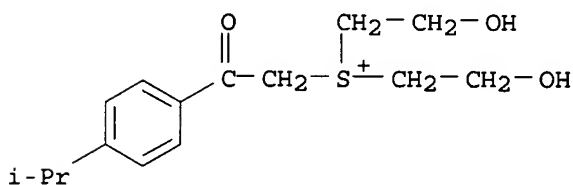
DOCUMENT TYPE:

Patent

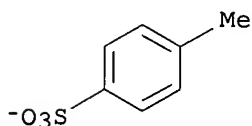
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 09328506	A2	19971222	JP 1996-146877	19960610

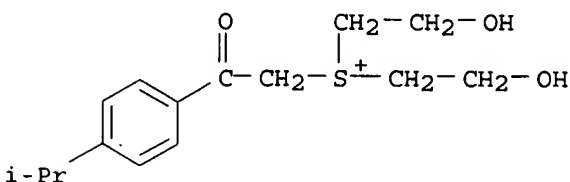
PRIORITY APPLN. INFO.:
OTHER SOURCE(S): MARPAT 128:115380
IT 201295-29-6 201295-56-9
RL: CAT (Catalyst use); USES (Uses)
(sulfonium complex polymerization initiators, its compns., and curable compns. thereof)
RN 201295-29-6 HCAPLUS
CN Sulfonium, bis(2-hydroxyethyl) [2-[4-(1-methylethyl)phenyl]-2-oxoethyl]-, salt with 4-methylbenzenesulfonic acid (1:1) (9CI) (CA INDEX NAME)
CM 1
CRN 201294-99-7
CMF C15 H23 O3 S



CM 2
CRN 16722-51-3
CMF C7 H7 O3 S

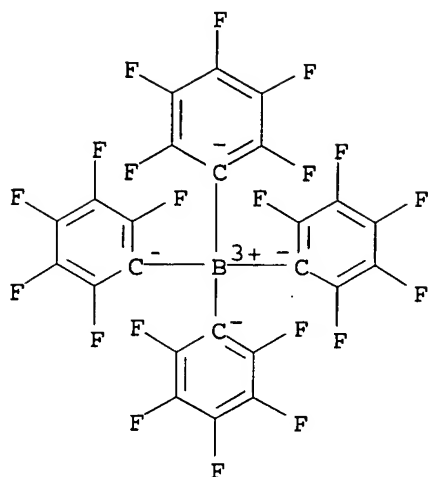


RN 201295-56-9 HCAPLUS
CN Sulfonium, bis(2-hydroxyethyl) [2-[4-(1-methylethyl)phenyl]-2-oxoethyl]-, tetrakis(pentafluorophenyl)borate(1-) (9CI) (CA INDEX NAME)
CM 1
CRN 201294-99-7
CMF C15 H23 O3 S

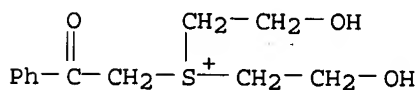


CM 2
CRN 47855-94-7
CMF C24 B F20

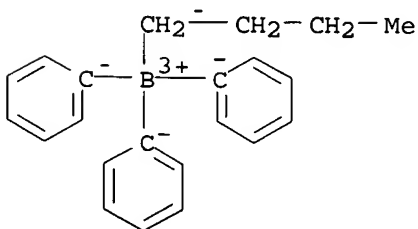
CCI CCS



IT 201294-96-4P
 RL: CAT (Catalyst use); IMF (Industrial manufacture); PREP (Preparation);
 USES (Uses)
 (sulfonium complex polymerization initiators, its compns., and curable compns. thereof)
 RN 201294-96-4 HCAPLUS
 CN Sulfonium, bis(2-hydroxyethyl) (2-oxo-2-phenylethyl)-, (T-4)-butyltriphenylborate(1-) (9CI) (CA INDEX NAME)
 CM 1
 CRN 201294-87-3
 CMF C12 H17 O3 S



CM 2
 CRN 47252-39-1
 CMF C22 H24 B
 CCI CCS



L16 ANSWER 10 OF 12 HCAPLUS COPYRIGHT 2005 ACS on STN
 ACCESSION NUMBER: 1997:784233 HCAPLUS
 DOCUMENT NUMBER: 128:76169
 TITLE: Radically polymerizable compositions and their cured products
 INVENTOR(S): Toba, Yasumasa

PATENT ASSIGNEE(S): Toyo Ink Mfg. Co., Ltd., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 35 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 09316117	A2	19971209	JP 1996-139823	19960603
PRIORITY APPLN. INFO.:			JP 1996-139823	19960603

OTHER SOURCE(S): MARPAT 128:76169

IT 194470-21-8

RL: CAT (Catalyst use); USES (Uses)

(polymerization initiators; radical polymerizable compns. containing generated acid-removable polymerization initiators)

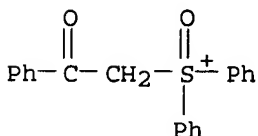
RN 194470-21-8 HCAPLUS

CN Sulfoxonium, (2-oxo-2-phenylethyl)diphenyl-, tetrakis(pentafluorophenyl)borate(1-) (9CI) (CA INDEX NAME)

CM 1

CRN 80621-37-0

CMF C20 H17 O2 S

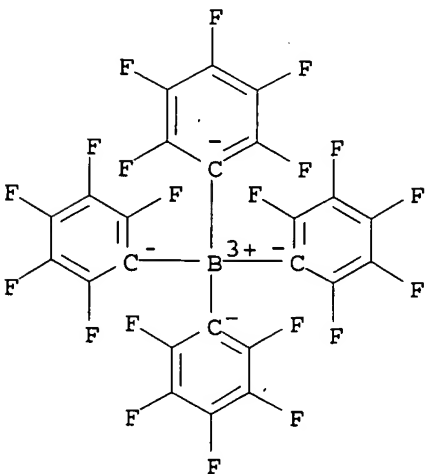


CM 2

CRN 47855-94-7

CMF C24 B F20

CCI CCS



L16 ANSWER 11 OF 12 HCAPLUS COPYRIGHT 2005 ACS on STN

ACCESSION NUMBER: 1997:762055 HCAPLUS

DOCUMENT NUMBER: 128:95393

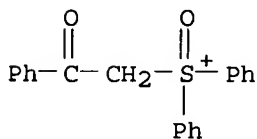
TITLE: Positive-working radiation-sensitive composition using onium borate complex as acid-generating agent

INVENTOR(S): Toba, Yasumasa; Tanaka, Yasuhiro; Yasuike, Madoka

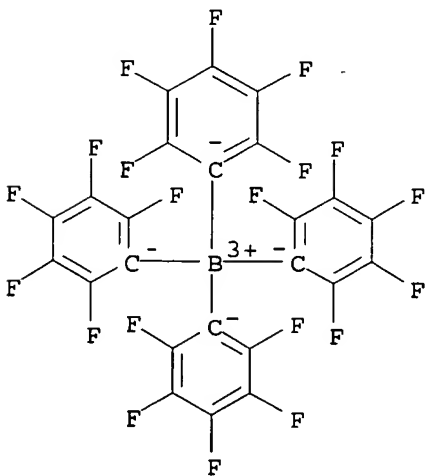
PATENT ASSIGNEE(S): Toyo Ink Mfg. Co., Ltd., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 33 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 09304931	A2	19971128	JP 1996-117204	19960513
JP 3605939	B2	20041222		

PRIORITY APPLN. INFO.: JP 1996-117204 19960513
 OTHER SOURCE(S): MARPAT 128:95393
 IT 194470-21-8
 RL: DEV (Device component use); USES (Uses)
 (radiation-sensitive composition containing onium borate as acid generator)
 RN 194470-21-8 HCAPLUS
 CN Sulfoxonium, (2-oxo-2-phenylethyl)diphenyl-, tetrakis(pentafluorophenyl)bo
 rate(1-) (9CI) (CA INDEX NAME)
 CM 1
 CRN 80621-37-0
 CMF C20 H17 O2 S



CM 2
 CRN 47855-94-7
 CMF C24 B F20
 CCI CCS



L16 ANSWER 12 OF 12 HCAPLUS COPYRIGHT 2005 ACS on STN
 ACCESSION NUMBER: 1997:509333 HCAPLUS
 DOCUMENT NUMBER: 127:206410
 TITLE: Sulfoxonium borates as energy-sensitive
 acid-generating agents, their compositions, curable
 compositions using the agents, and hybrid curable

INVENTOR(S): compositions
Toba, Yasumasa; Tanaka, Yasuhiro; Yasuike, Madoka
PATENT ASSIGNEE(S): Toyo Ink Mfg. Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 51 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 09194820	A2	19970729	JP 1996-4455	19960116
PRIORITY APPLN. INFO.:			JP 1996-4455	19960116
OTHER SOURCE(S):	MARPAT 127:206410			

IT 194470-21-8

RL: CAT (Catalyst use); USES (Uses)
(acid-generating agents; sulfoxonium borates as acid-generating agents
for photosensitive curable resin compns.)

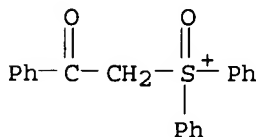
RN 194470-21-8 HCAPLUS

CN Sulfoxonium, (2-oxo-2-phenylethyl)diphenyl-, tetrakis(pentafluorophenyl)bo
rate(1-) (9CI) (CA INDEX NAME)

CM 1

CRN 80621-37-0

CMF C20 H17 O2 S

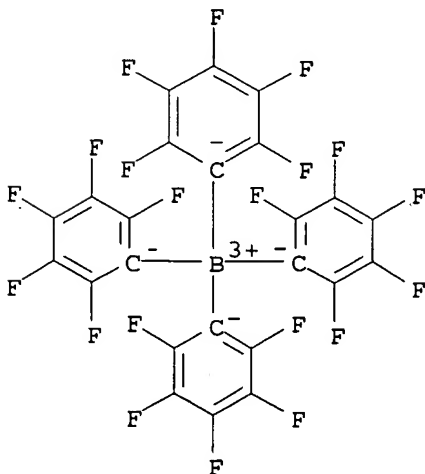


CM 2

CRN 47855-94-7

CMF C24 B F20

CCI CCS



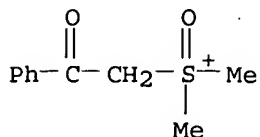
IT 194470-13-8P

RL: CAT (Catalyst use); IMF (Industrial manufacture); PREP (Preparation);
USES (Uses)
(acid-generating agents; sulfoxonium borates as acid-generating agents
for photosensitive curable resin compns.)

RN 194470-13-8 HCAPLUS
CN Sulfoxonium, dimethyl(2-oxo-2-phenylethyl)-, tetrakis[3,5-bis(trifluoromethyl)phenyl]borate(1-) (9CI) (CA INDEX NAME)

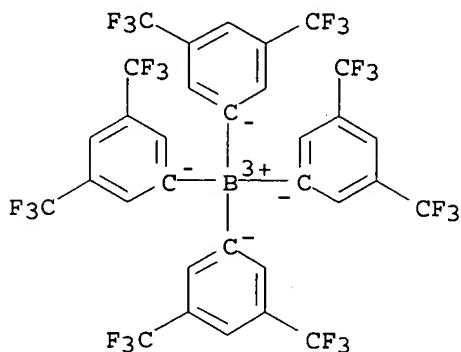
CM 1

CRN 80621-42-7
CMF C10 H13 O2 S



CM 2

CRN 79230-20-9
CMF C32 H12 B F24
CCI CCS



=> file reg

COST IN U.S. DOLLARS

FULL ESTIMATED COST

SINCE FILE	TOTAL
ENTRY	SESSION
53.47	55.39

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* effective March 20, 2005. A new display format, IDERL, is now *
* available and contains the CA role and document type information. *
*

Crossover limits have been increased. See HELP CROSSOVER for details.

Experimental and calculated property data are now available. For more
information enter HELP PROP at an arrow prompt in the file or refer
to the file summary sheet on the web at:
<http://www.cas.org/ONLINE/DBSS/registryss.html>

=> s 761458-97-3
L17 1 761458-97-3
(761458-97-3/RN)

=> 761458-93-9
761458-93-9 IS NOT A RECOGNIZED COMMAND
The previous command name entered was not recognized by the system.
For a list of commands available to you in the current file, enter
"HELP COMMANDS" at an arrow prompt (=>).

=> s 761458-93-9
L18 1 761458-93-9
(761458-93-9/RN)

	SINCE FILE	TOTAL
COST IN U.S. DOLLARS	ENTRY	SESSION
FULL ESTIMATED COST	0.43	55.82

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=> s 117 or 118
L19 3 L17 OR L18

=> duplicates remove 119
DUPLICATE PREFERENCE IS 'HCAPLUS, CAPLUS, USPATFULL'
KEEP DUPLICATES FROM MORE THAN ONE FILE? Y/(N):n
PROCESSING COMPLETED FOR L19
L20 1 DUPLICATE REMOVE L19 (2 DUPLICATES REMOVED)

=> d 120 ibib hitstr

L20 ANSWER 1 OF 1 HCAPLUS COPYRIGHT 2005 ACS on STN DUPLICATE 1
ACCESSION NUMBER: 2004:780222 HCAPLUS
DOCUMENT NUMBER: 141:304282
TITLE: Stimulus sensitive compound such as light-sensitive
acid or radical precursors and stimulus sensitive
composition containing the same
INVENTOR(S): Kodama, Kunihiro; Takahashi, Hyou
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: U.S. Pat. Appl. Publ., 56 pp.
CODEN: USXXCO
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 2004185378	A1	20040923	US 2004-799864	20040315
JP 2004277303	A2	20041007	JP 2003-68447	20030313
PRIORITY APPLN. INFO.:			JP 2003-68447	A 20030313

OTHER SOURCE(S): MARPAT 141:304282

IT 761458-97-3P

RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(stimulus sensitive compound)

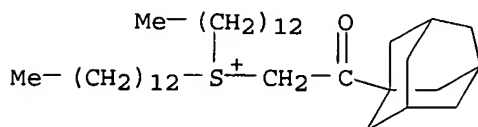
RN 761458-97-3 HCAPLUS

CN Sulfonium, (2-oxo-2-tricyclo[3.3.1.1^{3,7}]dec-1-ylethyl)ditridecyl-, salt with trifluoromethanesulfonic acid (1:1) (9CI) (CA INDEX NAME)

CM 1

CRN 761458-95-1

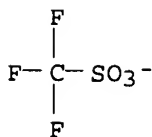
CMF C38 H71 O S



CM 2

CRN 37181-39-8

CMF C F3 O3 S



=> file reg

COST IN U.S. DOLLARS

FULL ESTIMATED COST

SINCE FILE ENTRY	TOTAL SESSION
7.73	63.55

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STRUCTURE FILE UPDATES: 22 MAY 2005 HIGHEST RN 850859-04-0

DICTIONARY FILE UPDATES: 22 MAY 2005 HIGHEST RN 850859-04-0

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*
* The CA roles and document type information have been removed from *
* the IDE default display format and the ED field has been added, *
* effective March 20, 2005. A new display format, IDERL, is now *
* available and contains the CA role and document type information. *
*

Crossover limits have been increased. See HELP CROSSOVER for details.

Experimental and calculated property data are now available. For more information enter HELP PROP at an arrow prompt in the file or refer to the file summary sheet on the web at:

<http://www.cas.org/ONLINE/DBSS/registryss.html>

=> s 761458-95-1

L21 1 761458-95-1
(761458-95-1/RN)

=> FIL HCAPLUS, CAPLUS, USPATFULL

COST IN U.S. DOLLARS	SINCE FILE ENTRY	TOTAL SESSION
FULL ESTIMATED COST	0.43	63.98

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=> s 121

L22 0 L21